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LITHOGRAPHY SYSTEM AND METHOD

ABSTRACT OF THE DISCLOSURE

A lithography system of in-line type includes environment sensors disposed within a chamber in which an exposure apparatus body is housed and a chamber in which a coater/developer body is housed. During a lithography process, on the basis of measured values such as air pressure temperature and humidity measured by the environment sensors, an environment control portion controls air conditioning portions in such a manner that the environmental conditions in the chambers becomes substantially the same as each other. Whereby, even when a wafer is transferred through a connecting portion, the environmental conditions in the chambers do not badly influence each other.